



NANOCLEAN 2018

Slightly alkaline liquid used in ultrasonic for the removal of cerium oxide, aluminium oxide, surfacing residues and fingerprints.

COMPATIBILITY:

- Precision optics: BK7/Quartz/Si/RG 665/Saphir/S-BSM16/N-LAK10/N-LAK22...
- Germanium/ZnS/Zerodur
- Sapphire
- Ophthalmic lenses (high and low index)
- Brass
- Stainless steel

COMPONENTS:

- Surfactants
- No chelating agents and no phosphates

PHYSICO-CHEMICAL DATA:

- pH concentrated: 9.5
- pH (1%): 9.4
- Density: 1.031
- Surface tension: 27.4 mN/m

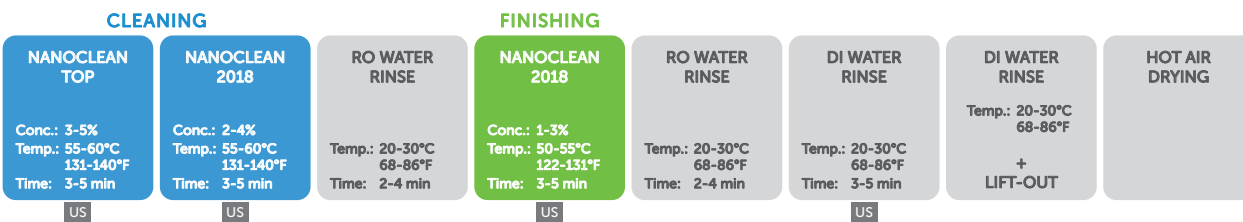
INSTRUCTIONS FOR USE:

The baths must be prepared using demineralised, osmosis or soft water. Optimum use conditions may be affected by the quality of the water used in the baths, as well as the type and quantity of contaminants.

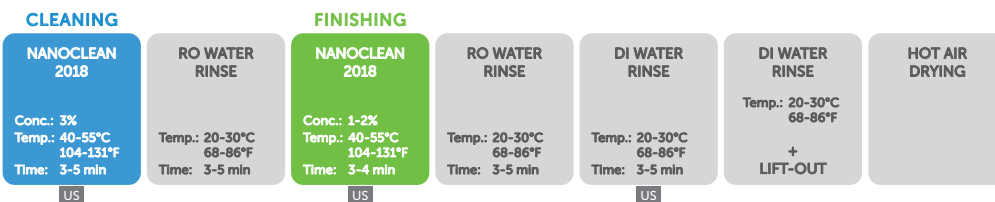
- Concentration: 1 to 5%
- Temperature: 40 to 60°C (104 to 140°F)
- Time: 3 to 5 minutes

PROCESS EXAMPLES:

Cleaning of mineral and organic lenses after surfacing and prior to control:



Preparation prior to anti-reflective coating:



If you have any questions, please contact our Application Centre on: +41 22 365 46 66

BENEFITS:

- Effective on a large range of polishing pastes
- Complete removal of surfacing agents
- Compatible with substrates sensitive to phosphates, alkaline or acidic chemical agents
- Adapted to sensitive lenses (< 1mS/cm)
- Does not damage lacquers
- Excellent wettability of surfaces
- No harmful components

20/04/21

STORAGE CONDITIONS:

- Keep the recipient hermetically sealed between 5°C and 40°C (41°F and 104°F) in a dry place.
- Always keep in packaging made from the same material as the original packaging.

